

POLOS[®] HOTPLATE 350

Our all NEW table-top hotplate is a versatile and affordable tool for R&D and pilot lines. It is designed with a hinged lid with N2 connector and is suitable for soft bake as well as hard bake processes, and curing of photoresist, epoxy or any other work requiring precise temperature control. The POLOS[®] Hotplate 350 also has upgradeable options, including lifting pins, vacuum bake and proximity pins.

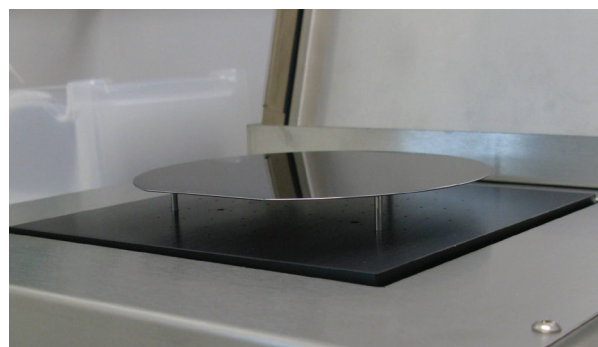
NEW!



Also available with a
200 x 200 mm heating area!

HOTPLATE 350 ADVANCED

- Temperature Range 50 - 230°C
- Programmable storage of 20 programs (Temperature/Time)
- Countdown timer (1-999 sec.) with acoustic alarm
- Temperature Uniformity $\pm 0.5^{\circ}\text{C}$
- Heater Surface Area 350 x 350 mm
- Suitable for 1 x 300 mm Wafer
- Equipped with programmable (electric) Lifting Pins set in radius to be defined
- Equipped with Proximity Pins to hold the wafer above the heating plate while baking
- Equipped with perforated vacuum plate to realize a hard contact bake
- Heater Block Material: Aluminum (anodized)
- Housing Material: Stainless Steel
- Including Hinged Lid with N2 connection
- Weight: 20kgs



The system is designed to work with process temperatures between 50°C - 230°C.

